

## ABSTRACT

2 A method for annealing a structure formed by electrodeposition is provided, the  
3 method comprising providing the electrodeposition structure, the electrodeposition  
4 structure comprising an electroformed mold, the electroformed mold having a nominal  
5 thickness between and including 0.5mm to 8.0mm and having a melting temperature;  
6 heating the electrodeposition structure to a temperature between ambient temperature and  
7 the melting temperature of the electrodeposition structure; isostatically pressurizing the  
8 electrodeposition structure to a pressure above ambient pressure; cooling the  
9 electrodeposition structure to ambient temperature; and depressurizing the  
10 electrodeposition structure to ambient pressure.

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